

| Application/Control No. | Applicant(s)/Patent under Reexamination | |
|-------------------------|---|--|
| 10/540,389 | TAKEI ET AL. | |
| Examiner | Art Unit | |
| Ling-Siu Choi | 1713 | |

| SEARCHED | | | | | |
|----------|----------|-----------|----------|--|--|
| Class | Subclass | Date | Examiner | | |
| 526 | 307.5 | 10/2/2007 | LSC | | |
| | 317.1 | | | | |
| 430 | 271.1 | | | | |
| | 270.1 | | , | | |
| | | | | | |
| | | | | | |
| | | | | | |
| | | | | | |
| | | | | | |
| | | | | | |
| | | | | | |
| | | | | | |
| | | | | | |
| | | | | | |

| INTERFERENCE SEARCHED | | | | | |
|-----------------------|----------|------|----------|--|--|
| Class | Subclass | Date | Examiner | | |
| | | | | | |
| | | | | | |
| | | | | | |
| | <u> </u> | | | | |
| | | | | | |
| | | | | | |

| SEARCH NO (INCLUDING SEARCH | |) |
|--|-----------|------|
| | DATE | EXMR |
| West | 10/2/2007 | LSC |
| crosslinker-polymer with hydroxy or carboxy- semiconductor-gap fill-antireflective | | |
| | | |
| | | |
| | | |
| | | |
| | | |
| | | |
| | | |